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[Stamp: Miyazaki, 6/19/02, Mototsugu]

NOTIFICATION OF REASONS FOR REJECTION

Patent Application No.: Patent Application No. 2000-097370
Draft Date: June 12, 2002
Patent Office Examiner: Kazumitsu Kudo 9274 5W00
Agent of Patent Applicant: Chikara Miyazaki
Applicable Sections: Section 29 (2)

The present application should be rejected for the following reasons. If you have an opinion concerning this, please submit a statement of opinion within 60 days of the date of dispatch of this notification.

Reasons

The inventions according to Claims 1 through 4 of the present application are inventions that could have easily been invented prior to the filing of the application by a person having an ordinary knowledge of the technical field to which the inventions belong on the basis of inventions described in Publications (1) and (2) below, which were disseminated in Japan or in foreign countries prior to the filing of the application. Thus, in accordance with the provisions of Section 29 (2) of the Patent Law, these inventions cannot be patented.

Note

(1) Japanese Patent Application Kokai No. H 8-181558 [for example, see the description relating to Figure 2 concerning the ion gun 9 and driving mechanism 14].

(2) Japanese Patent Application Kokai No. H 6-57451 [for example, see the description relating to Figure 1 concerning the treatment chamber 4 and ion source 13].

Furthermore, in the method described in Cited Example 1, the fact that the electronic part element or ion beam, or both, are moved in the direction within the plane of the surface on which the electrodes of the aforementioned electronic part element are formed during the ion beam irradiation process is recognized as something that could easily be devised by a person skilled in the art.

Record of Results of Survey of Prior Art References

• Field surveyed: IPC 7th Edition H 03 H 3/10 H 03 H 3/04

[Stamp: —, 6/24/02, Hayashi]